

## Contents

<b>Foreword</b>	V
<b>Preface</b>	XVII
<b>Introduction</b>	XXI
<b>List of Contributors</b>	XXXIII

### Part One Introduction to ALD 1

<b>1</b>	<b>Theoretical Modeling of ALD Processes</b>	3
	<i>Charles B. Musgrave</i>	
1.1	Introduction	3
1.2	Overview of Atomistic Simulations	3
1.2.1	Quantum Simulations	4
1.2.2	Wave Function-Based Quantum Simulations	5
1.2.3	Density Functional-Based Quantum Simulations	6
1.2.4	Finite and Extended Quantum Simulations	8
1.2.5	Basis Set Expansions	9
1.3	Calculation of Properties Using Quantum Simulations	10
1.3.1	Calculation of Transition States and Activation Barriers	10
1.3.2	Calculation of Rates of Reaction	12
1.4	Prediction of ALD Chemical Mechanisms	13
1.4.1	Gas-Phase Reactions in ALD	14
1.4.2	Surface Reactions in ALD	14
1.4.2.1	Adsorption Reactions in ALD	14
1.4.2.2	Ligand Exchange Reactions	15
1.5	Example of a Calculated ALD Mechanism: ALD of Al <sub>2</sub> O <sub>3</sub> Using TMA and Water	16
	References	20
<b>2</b>	<b>Step Coverage in ALD</b>	23
	<i>Sovan Kumar Panda and Hyunjung Shin</i>	
2.1	Introduction	23
2.2	Growth Techniques	24
2.3	Step Coverage Models in ALD	28

2.3.1	Gordon's Model for Step Coverage	28
2.3.1.1	Parameters for Step Coverage	28
2.3.2	Kim's Model for Step Coverage	31
2.4	Experimental Verifications of Step Coverage Models	34
2.5	Summary	38
	References	38
<b>3</b>	<b>Precursors for ALD Processes</b>	<b>41</b>
	<i>Matti Putkonen</i>	
3.1	Introduction	41
3.2	General Requirements for ALD Precursors	42
3.3	Metallic Precursors for ALD	42
3.3.1	Inorganic Precursors	44
3.3.1.1	Elemental Precursors	44
3.3.1.2	Halides	44
3.3.1.3	Oxygen-Coordinated Compounds	44
3.3.1.4	Nitrogen-Coordinated Precursors	46
3.3.1.5	Precursors Coordinated through Other Inorganic Elements	46
3.3.2	Organometallic ALD Precursors	47
3.3.2.1	Metal Alkyls	47
3.3.2.2	Cyclopentadienyl-Type Compounds	47
3.3.2.3	Other Organometallic Precursors	49
3.4	Nonmetal Precursors for ALD	49
3.4.1	Reducing Agents	49
3.4.2	Oxygen Sources	49
3.4.3	Nitrogen Sources	50
3.4.4	Sulfur and Other Chalcogenide Precursors	50
3.5	Conclusions	50
	References	51
<b>4</b>	<b>Sol–Gel Chemistry and Atomic Layer Deposition</b>	<b>61</b>
	<i>Guyhaine Clavel, Catherine Marichy, and Nicola Pinna</i>	
4.1	Aqueous and Nonaqueous Sol–Gel in Solution	61
4.1.1	Aqueous Sol–Gel	61
4.1.1.1	Introduction	61
4.1.1.2	Development of Sol–Gel Chemistry	61
4.1.2	Nonaqueous Sol–Gel	62
4.1.2.1	Introduction	62
4.1.2.2	Synthesis of Nanomaterials	63
4.2	Sol–Gel and ALD: An Overview	63
4.2.1	Metal Oxide Formation via Hydrolytic Routes	64
4.2.1.1	Reaction with Metal Halides	64
4.2.1.2	Reaction with Metal Alkoxide	65
4.2.1.3	Reaction with Organometallic Compounds	66
4.2.2	Metal Oxide Deposition under Nonaqueous Conditions	67

4.2.2.1	Alkyl Halide Elimination	67
4.2.2.2	Ether Elimination	68
4.2.2.3	Ester Elimination	68
4.2.2.4	Other Reactions	69
4.2.3	Concluding Remarks	69
4.3	Mechanistic and <i>In Situ</i> Studies	70
4.3.1	General Considerations	71
4.3.1.1	Differences between Sol–Gel in Solution and in ALD	71
4.3.1.2	Reaction Mechanism Study	71
4.3.2	Comparison of Selected Reactions	72
4.3.2.1	Case of the Silica Deposition	72
4.3.2.2	Case of Alkyl Halide Condensation	75
4.3.3	Conclusions	76
	References	76
<b>5</b>	<b>Molecular Layer Deposition of Hybrid Organic–Inorganic Films</b>	<b>83</b>
	<i>Steven M. George, B. Yoon, Robert A. Hall, Aziz I. Abdulagatov, Zachary M. Gibbs, Younghee Lee, Dragos Seghete, and Byoung H. Lee</i>	
5.1	Introduction	83
5.2	General Issues for MLD of Hybrid Organic–Inorganic Films	85
5.3	MLD Using Trimethylaluminum and Ethylene Glycol in an AB Process	87
5.4	Expansion to an ABC Process Using Heterobifunctional and Ring-Opening Precursors	89
5.5	Use of a Homotrifunctional Precursor to Promote Cross-Linking in an AB Process	93
5.6	Use of a Heterobifunctional Precursor in an ABC Process	96
5.7	MLD of Hybrid Alumina–Siloxane Films Using an ABCD Process	99
5.8	Future Prospects for MLD of Hybrid Organic–Inorganic Films	103
	References	106
<b>6</b>	<b>Low-Temperature Atomic Layer Deposition</b>	<b>109</b>
	<i>Jens Meyer and Thomas Riedl</i>	
6.1	Introduction	109
6.2	Challenges of LT-ALD	110
6.3	Materials and Processes	113
6.4	Toward Novel LT-ALD Processes	115
6.5	Thin Film Gas Diffusion Barriers	117
6.6	Encapsulation of Organic Electronics	119
6.6.1	Encapsulation of Organic Light Emitting Diodes	119
6.6.2	Encapsulation of Organic Solar Cells	123
6.7	Conclusions	125
	References	125

<b>7</b>	<b>Plasma Atomic Layer Deposition</b>	<b>131</b>
	<i>Erwin Kessels, Harald Profijt, Stephen Potts, and Richard van de Sanden</i>	
7.1	Introduction	131
7.2	Plasma Basics	134
7.3	Plasma ALD Configurations	139
7.4	Merits of Plasma ALD	142
7.5	Challenges for Plasma ALD	149
7.6	Concluding Remarks and Outlook	153
	References	154
<b>Part Two</b>	<b>Nanostructures by ALD</b>	<b>159</b>
<b>8</b>	<b>Atomic Layer Deposition for Microelectronic Applications</b>	<b>161</b>
	<i>Cheol Seong Hwang</i>	
8.1	Introduction	161
8.2	ALD Layers for Memory Devices	162
8.2.1	Mass Production Level Memories	162
8.2.1.1	Dynamic Random Access Memory	163
8.2.1.2	Flash Memory	168
8.2.1.3	Phase Change Memory	172
8.2.2	Emerging Memories	174
8.2.2.1	Ferroelectric Memory	175
8.2.2.2	Magnetic Random Access Memory	178
8.2.2.3	Resistive Random Access Memory	178
8.2.3	Three-Dimensional Stacked Memories	179
8.3	ALD for Logic Devices	180
8.3.1	Front End of the Line Process	180
8.3.2	Back End of the Line Process	185
8.4	Concluding Remarks	187
	References	188
<b>9</b>	<b>Nanopatterning by Area-Selective Atomic Layer Deposition</b>	<b>193</b>
	<i>Han-Bo-Ram Lee and Stacey F. Bent</i>	
9.1	Concept of Area-Selective Atomic Layer Deposition	193
9.2	Change of Surface Properties	195
9.2.1	Self-Assembled Monolayers	195
9.2.2	Polymers	201
9.2.3	Inherent Surface Reactivity	203
9.2.4	Vapor-Phase Deposition	204
9.3	Patterning	205
9.3.1	Surface Modification without Patterning	205
9.3.2	Microcontact Printing	205
9.3.3	Photolithography	207
9.3.4	Nanotemplating	212
9.3.5	Scanning Probe Microscopy	213

9.4	Applications of AS-ALD	215
9.5	Current Challenges	216
	References	218
<b>10</b>	<b>Coatings on High Aspect Ratio Structures</b>	<b>227</b>
	<i>Jeffrey W. Elam</i>	
10.1	Introduction	227
10.2	Models and Analysis	228
10.2.1	Analytical Method	229
10.2.2	Monte Carlo Simulations	229
10.3	Characterization Methods for ALD Coatings in High Aspect Ratio Structures	230
10.4	Examples of ALD in High Aspect Ratio Structures	232
10.4.1	Aspect Ratio of 10	232
10.4.1.1	Trenches	232
10.4.1.2	MEMS	233
10.4.2	Aspect Ratio of 100	234
10.4.2.1	Anodic Aluminum Oxide	234
10.4.2.2	Inverse Opals	237
10.4.3	Aspect Ratio of 1000 and Beyond	238
10.4.3.1	Silica gel	238
10.4.3.2	Aerogels	240
10.5	Nonideal Behavior during ALD in High Aspect Ratios	242
10.6	Conclusions and Future Outlook	245
	References	246
<b>11</b>	<b>Coatings of Nanoparticles and Nanowires</b>	<b>251</b>
	<i>Hong Jin Fan and Kornelius Nielsch</i>	
11.1	ALD on Nanoparticles	251
11.2	Vapor–Liquid–Solid Growth of Nanowires by ALD	254
11.3	Atomic Layer Epitaxy on Nanowires	256
11.4	ALD on Semiconductor NWs for Surface Passivation	257
11.5	ALD-Assisted Formation of Nanopeapods	258
11.6	Photocorrosion of Semiconductor Nanowires Capped by ALD Shell	260
11.7	Interface Reaction of Nanowires with ALD Shell	261
11.7.1	ZnO–Al <sub>2</sub> O <sub>3</sub>	261
11.7.2	ZnO–TiO <sub>2</sub>	262
11.7.3	ZnO–SiO <sub>2</sub>	264
11.7.4	MgO–Al <sub>2</sub> O <sub>3</sub>	265
11.8	ALD ZnO on NWs/Tubes as Seed Layer for Growth of Hyperbranch	265
11.9	Conclusions	267
	References	268

<b>12</b>	<b>Atomic Layer Deposition on Soft Materials</b>	<b>271</b>
	<i>Gregory N. Parsons</i>	
12.1	Introduction	271
12.2	ALD on Polymers for Passivation, Encapsulation, and Surface Modification	274
12.3	ALD for Bulk Modification of Natural and Synthetic Polymers and Molecules	279
12.4	ALD for Polymer Sacrificial Templating: Membranes, Fibers, and Biological and Optical Structures	280
12.5	ALD Nucleation on Patterned and Planar SAMs and Surface Oligomers	283
12.6	Reactions during Al <sub>2</sub> O <sub>3</sub> ALD on Representative Polymer Materials	286
12.6.1	Al <sub>2</sub> O <sub>3</sub> ALD on Polypropylene	286
12.6.2	Al <sub>2</sub> O <sub>3</sub> ALD on Polyvinyl Alcohol	288
12.6.3	Al <sub>2</sub> O <sub>3</sub> ALD on Polyamide 6	289
12.6.4	Mechanisms for Al <sub>2</sub> O <sub>3</sub> ALD on PP, PVA, and PA-6	290
12.7	Summary	291
	References	292
<b>13</b>	<b>Application of ALD to Biomaterials and Biocompatible Coatings</b>	<b>301</b>
	<i>Mato Knez</i>	
13.1	Application of ALD to Biomaterials	302
13.1.1	Protein-Based Nanostructures	302
13.1.1.1	Tobacco Mosaic Virus	302
13.1.1.2	Ferritin and Apoferritin	304
13.1.1.3	S-Layers	304
13.1.2	Peptide Assemblies	305
13.1.3	Natural Fibers	307
13.1.3.1	DNA	307
13.1.3.2	Collagen	308
13.1.3.3	Spider Silk	308
13.1.3.4	Cellulose Fibers from Paper	310
13.1.3.5	Cotton Fibers	310
13.1.3.6	Sea Mouse Bristles	311
13.1.4	Patterned Biomaterials	312
13.1.4.1	Butterfly Wings	312
13.1.4.2	Fly Eyes	314
13.1.4.3	Legumes	315
13.1.4.4	Water Strider Legs	315
13.1.5	Biomineralized Structures	316
13.2	Biocompatible Coatings	317
13.2.1	Biocompatibility of Alumina	317
13.2.2	Biocompatibility of Titania	318
13.2.3	Biocompatibility of Hydroxyapatite	318

13.2.4	Biocompatibility of Pt-, TiO <sub>2</sub> -, or ZnO-Coated Porous Alumina	318
13.2.5	Biocompatibility of TiN-Coated Cotton Fabrics	319
13.3	Summary	320
	References	321
<b>14</b>	<b>Coating of Carbon Nanotubes</b>	<b>327</b>
	<i>Catherine Marichy, Andrea Pucci, Marc-Georg Willinger, and Nicola Pinna</i>	
14.1	Introduction	327
14.2	Purification and Surface Functionalization of Carbon Nanotubes	328
14.3	Decoration/Coating of Carbon Nanotubes by Solution Routes	329
14.3.1	<i>In Situ</i> Coating	329
14.3.2	Attachment of Preformed Nanobuilding Blocks	330
14.4	Decoration/Coating of Carbon Nanotubes by Gas-Phase Techniques	330
14.5	Atomic Layer Deposition on Carbon Nanotubes	331
14.6	Coating of Large Quantity of CNTs by ALD	337
14.7	ALD Coating of Other sp <sup>2</sup> -Bonded Carbon Materials	338
14.8	Conclusions	340
	References	340
<b>15</b>	<b>Inverse Opal Photonics</b>	<b>345</b>
	<i>Davy P. Gaillot and Christopher J. Summers</i>	
15.1	Introduction and Background	345
15.2	Properties of Three-Dimensional Photonic Band Structures	349
15.2.1	Synthetic Opals and Inverse Opals	349
15.3	Large-Pore and Non-Close-Packed Inverse Opals	352
15.4	Experimental Studies	353
15.4.1	Inversion of Opal Structures	353
15.4.2	Atomic Layer Deposition	357
15.4.3	Multilayer Fabrication Steps for Advanced Photonic Crystals	360
15.5	Tunable PC Structures	366
15.6	Summary	369
	References	371
<b>16</b>	<b>Nanolaminates</b>	<b>377</b>
	<i>Adriana V. Szeghalmi and Mato Knez</i>	
16.1	Introduction	377
16.2	Optical Applications	377
16.2.1	Interference Optics	377
16.2.2	Diffraction Optical Elements	381
16.3	Thin Film Encapsulation	383
16.4	Applications in Electronics	386
16.4.1	Dielectric Properties of Inorganic Nanolaminates	387
16.4.2	Dielectric Properties of Organic–Inorganic Nanolaminates	390

16.4.3	Applications for Memories	391
16.5	Copper Electroplating Applications	392
16.6	Solid Oxide Fuel Cells	393
16.7	Complex Nanostructures	394
16.8	Summary	395
	References	396
<b>17</b>	<b>Challenges in Atomic Layer Deposition</b>	<b>401</b>
	<i>Markku Leskelä</i>	
17.1	Introduction	401
17.2	Metals	402
17.3	Nonmetal Elements	404
17.4	Binary Compounds	406
17.4.1	Oxides	406
17.4.2	Nitrides	408
17.4.3	Other III–V Compounds	410
17.4.4	Carbides	410
17.4.5	Silicides and Borides	412
17.4.6	Halides	412
17.4.7	Compounds with Oxoanions	413
17.5	Ternary and Quaternary Compounds	414
17.6	Nucleation	415
17.7	Conclusions	416
	References	417
	<b>Index</b>	<b>423</b>